

Line Number	Hits	Search Text	IP	Time	Claim
1	174	hardmask or "hard mask" or SiN or "silicon nitride" same API or antireflect or "anti reflective coating" or hardmask or "hard mask" or SiN or "silicon nitride" same API or antireflect or "anti reflective coating" same etch\$3	USPAT; IBM_TDB	2003/04/14 09:51	
2	143	resist or photoresist or pattern or patterned or patterning same API or antireflect or "anti reflective coating"	USPAT; IBM_TDB	2003/04/14 09:51	
3	570	resist or photoresist or pattern or patterned or patterning with API or antireflect or "anti reflective coating"	USPAT; IBM_TDB	2003/04/14 09:51	
4	897	resist or photoresist or pattern or patterned or patterning with API or antireflect or "anti reflective coating" same etch\$3	USPAT; IBM_TDB	2003/04/14 09:51	
5	192	hardmask or "hard mask" or SiN or "silicon nitride" same photoresist or photoresist or pattern or patterned or patterning with API or antireflect or "anti reflective coating" same etch\$3	USPAT; IBM_TDB	2003/04/14 09:51	
6	427	resist or photoresist or pattern or patterned or patterning with API or antireflect or "anti reflective coating" same etch\$3 and 4:8/3:6:1:1:1	USPAT; IBM_TDB	2003/04/14 09:51	
7	1055	hardmask or "hard mask" or SiN or "silicon nitride" with API or antireflect or "anti reflective coating"	USPAT; IBM_TDB	2003/04/14 09:51	
8	138	resist or photoresist or pattern or patterned or patterning same hardmask or "hard mask" or SiN or "silicon nitride" with API or antireflect or "anti reflective coating" same etch\$3	USPAT; IBM_TDB	2003/04/14 09:51	
9	4672	: pattern or patterned or patterning with API or antireflect or "anti reflective coating":	USPAT; IBM_TDB	2003/04/14 09:52	
10	481	: pattern or patterned or patterning with API or antireflect or "anti reflective coating": with opening or via or contact	USPAT; IBM_TDB	2003/04/14 09:51	
11	1208	: pattern or patterned or patterning same API or antireflect or "anti reflective coating" same photoresist or photoresist	USPAT; IBM_TDB	2003/04/14 09:53	
12	740	: pattern or patterned or patterning with API or antireflect or "anti reflective coating" with resist or photoresist	USPAT; IBM_TDB	2003/04/14 09:51	
13	11	: pattern or patterned or patterning with API or antireflect or "anti reflective coating" same photoresist or photoresist	USPAT; IBM_TDB	2003/04/14 09:51	
14	104	: pattern or patterned or patterning with API or antireflect or "anti reflective coating" same photoresist or photoresist	USPAT; IBM_TDB	2003/04/14 09:51	
15	104	: pattern or patterned or patterning with API or antireflect or "anti reflective coating" same photoresist or photoresist	USPAT; IBM_TDB	2003/04/14 09:51	
16	104	: opening or contact with API or antireflect or "anti reflective coating" or BAP	USPAT; IBM_TDB	2003/04/14 09:51	
17	104	: opening or contact with API or antireflect or "anti reflective coating" or BAP same etch\$3	USPAT; IBM_TDB	2003/04/14 09:51	
18	438	: opening or contact with API or antireflect or "anti reflective coating" or BAP same etch\$3	USPAT; IBM_TDB	2003/04/14 09:51	
19	438	: opening or contact with API or antireflect or "anti reflective coating" or BAP same etch\$3	USPAT; IBM_TDB	2003/04/14 09:51	